



THE CATHOLIC UNIVERSITY OF EASTERN AFRICA

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MAIN EXAMINATION

MAY – JULY 2019 TRIMESTER

FACULTY OF SCIENCE

DEPARTMENT OF PHYSICS

SPECIAL / SUPPLEMENTARY EXAMINATION

PHY 307: PHYSICAL ELECTRONICS

Date: JULY 2019

Duration: 2 Hours

INSTRUCTIONS: Answer Question ONE and any other Two Questions

Constants

Electron charge $q = 1.6 \times 10^{-19} \text{ C}$

Mobility of electron in Silicon $\mu_e = 0.145 \text{ m}^2/\text{V.s}$

Mobility of holes in Silicon $\mu_p = 0.05 \text{ m}^2/\text{V.s}$

Mobility of electrons in Germanium $\mu_e = 0.38 \text{ m}^2/\text{V.s}$

Mobility of holes in Germanium $\mu_p = 0.18 \text{ m}^2/\text{V.s}$

Boltzmann constant $k = 1.38 \times 10^{-23} \text{ J/K}$

1. (a) i, Differentiate between a conductor and a semi- conductor? (2mks)
ii, What do you understand by the term “negative coefficient” (1mk)
iii, Explain the following terms;
➤ Acceptor ion
➤ Doping

➤ Mean lifetime (3mks)

(b) i, State the mass action law (1mk)

ii, Calculate the intrinsic conductivity of Silicon at room temperature

if $n_i = 1.41 \times 10^{16} \text{ m}^{-3}$, $\mu_e = 0.145 \text{ m}^2/\text{V} \cdot \text{s}$, $\mu_p = 0.05 \text{ m}^2/\text{V} \cdot \text{s}$ and

$q = 1.6 \times 10^{-19} \text{ C}$. What are the individual contributions made by electrons and holes. (8mks)

(c) i, Distinguish between forward and reverse biasing of a P-N junction. (2mks)

ii, State three applications of semi-conductor diodes in modern electronic circuitry? (3mks)

(d) i, Calculate the barrier potential at room temperature (300K) for a P-N junction in

Silicon which is doped to a carrier density of 10^{21} m^{-3} on the P- side and 10^{22} m^{-3}

On the N- side. The intrinsic carrier density for Silicon is $1.4 \times 10^{16} \text{ m}^{-3}$. (4mks)

(e) A specimen of Silicon is 0.2mm long and a cross sectional area of $0.2 \times 0.2 \text{ mm}$. One Volt is impressed across the bar results in a current of 8mA. Assuming that the current is due to electrons, calculate

i, Concentration of free electrons

ii, Drift velocity given at 300K, $\mu_n = 1300 \text{ m}^2/\text{V} \cdot \text{s}$ and $q = 1.6 \times 10^{-19} \text{ C}$ (6mks)

2.(a) Find the length of a round copper wire of diameter 1mm which will have a resistance of 1Ω and conductivity $1.58 \times 10^7 \text{ S/m}$. If the wire is subjected to an electric field of 10 mV/m , What is the current density? (7mks)

(b) A conduction wire has a resistivity of $1.54 \times 10^{-8} \Omega \text{ m}$ at room temperature. There are 5.8×10^{28} conduction electrons per m^3 . Calculate the mobility of the electrons. (5mks)

(c) The mobility of free electrons and holes in pure germanium are 0.38 and $0.18 \text{ m}^2/\text{V} \cdot \text{s}$, The corresponding values in Silicon are 0.13 and $0.05 \text{ m}^2/\text{V} \cdot \text{s}$ respectively. Find the value of intrinsic conductivity for both materials. Assume $n_i = 2.5 \times 10^{19} / \text{m}^3$ for Ge and $1.5 \times 10^{16} / \text{m}^3$ for Si at room temperature. (8mks)

3. (a) From Fermi - Dirac probability distribution function, Show that for an intrinsic semiconductor, the Fermi level lie midway between the conduction and valence bands (10mks)

(b) A specimen of pure Germanium at 300K has a density of charge carriers of $2.5 \times 10^{19} \text{ m}^{-3}$. Its doped with a donor impurity atoms at the rate of one atom for every 10^6 atoms of Germanium. All impurity atoms may be ionized. The density of Ge atom is $4.2 \times 10^{28} \text{ atoms/m}^3$. Find the resistivity of the doped germanium if the electron mobility is $0.36 \text{ m}^2/\text{V.s}$ (5mks)

(c) Silicon is doped with acceptor atoms to a density of 10^{22} m^{-3} . If its assumed that all acceptor centres are ionized, calculate the conductivity of extrinsic silicon. Given that intrinsic density is $1.4 \times 10^{16} \text{ m}^{-3}$. $\mu_e = 0.145 \text{ m}^2/\text{V.s}$ $\mu_p = 0.05 \text{ m}^2/\text{V.s}$. (5mks)

4.(a) What do you understand by the terms

i, Potential barrier of a P-N junction (2mks)

ii, Bulk resistance of a semi-conductor material (2mks)

(b) Germanium diode has saturation current of $10 \mu\text{A}$ at room temperature 300K. Find the saturation current at 400K. (4mks)

(c) Show that the junction resistance for silicon or germanium diode is given by the equation;

$$r_j = \frac{26}{I_F} \text{ Where } I_F \text{ is the diode current in milliamperes. (12mks)}$$

5. (a) An intrinsic semi-conductor (Silicon) has $5 \times 10^{28} \text{ atoms/m}^3$ at 20°C room temperature. At this temperature, there are $1.5 \times 10^{16} \text{ electron-hole}$ pairs. Find the conductivity (σ) of silicon at 20°C . If the above material is doped with indium atoms at the rate of 1 atom per 10^7 silicon atoms, Find the conductivity of doped material at room temperature. If the conductivity increases at the rate of 5% per $^\circ\text{C}$ then find also the conductivity of doped silicon at 34°C ($\mu_e = 0.145 \text{ m}^2/\text{V.s}$, $\mu_p = 0.05 \text{ m}^2/\text{V.s}$, $K = 1.38 \times 10^{-23} \text{ J/K}$ $q = 1.6 \times 10^{-19} \text{ C}$) (10mks)

(b) Determine the germanium P-N junction diode current for a forward bias voltage of 0.22V at room temperature 25°C with a reverse saturation current equal to 1mA. Take $\eta = 1$ (5mks)

(c) A silicon diode has a bulk resistance of 2Ω and forward current of 12mA. What is the actual value of V_F for the device? (5mks)

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